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Change in reflectance spectrum of nanoporous silicon by gas adsorption

Young-You Kim, Jeong-Hwa Lee, Eun-Jun Ahn, Han-Jung Kim

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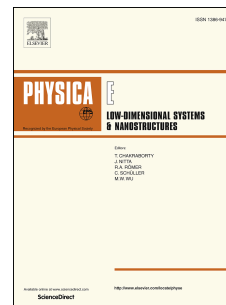
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Change in Reflectance Spectrum of Nanoporous Silicon by Gas AdsorptionYoung-You Kim^{a,*}, Jeong-Hwa Lee, Eun-Jun Ahn^a and Han-Jung Kim^{a,b,*}^a Department of Physics, Kongju National University, Gongju 32588, South Korea^b Center for Integrated Smart Sensors (CISS), Korea Advanced Institute of Science and Technology (KAIST), Daejeon 34141, South Korea*E-mail address: yykim@kongju.ac.kr (Y.-Y. Kim), hjkim0321@kaist.ac.kr (H.-J. Kim)**ABSTRACT**

In this paper, we propose a new strategy to improve the performance of nanoporous silicon (np-Si) layer-based optical gas sensors. For this, we fabricated the np-Si layer on a p⁺-type silicon substrate and modified the surface wettability of the np-Si layer with oxygen (O₂) plasma treatment. We then compared the changes in the reflectance spectra of the O₂ plasma-treated np-Si layer that had been exposed to various organic vapors with that of the untreated np-Si layer. The results by measuring the contact angle on the surface confirmed that the surface of the O₂ plasma-treated np-Si layer was hydrophilic. During the exposure to the organic vapors, there was a reversible red-shift phenomenon in the reflectance spectrum. This study confirmed that the red-shift can be attributed to the changes in the refractive index induced by the capillary condensation of the organic vapor within the nanopores of the np-Si

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